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**APPLICANTS

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** FOREIGN APPLICATIONS VERIFIED:

JAPAN 2000-395319 12/26/2000

PG-PUB DO NOT PUBLISH <input type="checkbox"/>	RESCIND <input type="checkbox"/>	ATTORNEY DOCKET NO 862.02476
Foreign priority claimed: <input type="checkbox"/> yes <input type="checkbox"/> no 35 USC 119 conditions met: <input type="checkbox"/> yes <input type="checkbox"/> no Verified and Acknowledged Examiners's initials:		
TITLE: Exposure apparatus, device manufacturing method, semiconductor manufacturing factory, and exposure apparatus maintenance method		

PAYMENT OF ALLOWANCE MAILED		Assistant Examiner		CLAIMS ALLOWED	
ISSUE FEE		Primary Examiner		Total Claims	
Due	Date Paid	PREPARED FOR ISSUE		DRAWINGS	
<input type="checkbox"/> TERMINAL DISCLAIMER		WARNING: The information disclosed herein may be restricted. Unauthorized disclosure may be prohibited by the United States Code Title 35, Sections 122, 181 and 368, Possession outside the U.S. Patent & Trademark Office is restricted to authorized employees and contractors only.		Sheets Drawn: Figures: Application Examiner	

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